

Lasers

lecture 10

Czesław Radzewicz

energy band structure in semiconductors

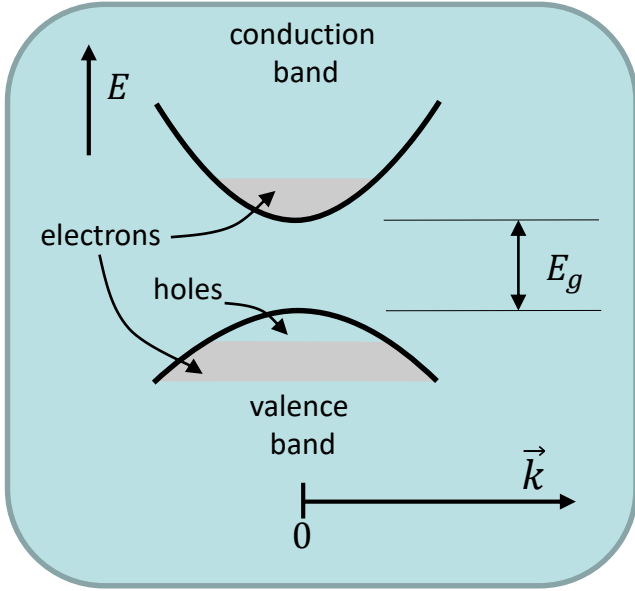
crystal lattice \Rightarrow periodic potential

electron wave function

$$\psi(\vec{r}) = u(\vec{r})e^{-i\vec{k}\cdot\vec{r}}$$

\uparrow
 periodic function

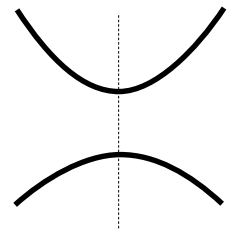
consequences:



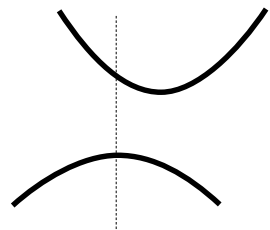
	E_g (eV)
C (diam.)	5.47
GaN	3.4
GaP	2.26
GaAs	1.43
Si	1.12
InSb	0.17

important distinction:

direct bandgap

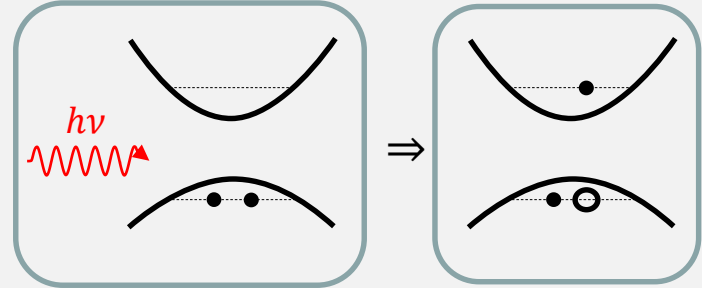


indirect bandgap

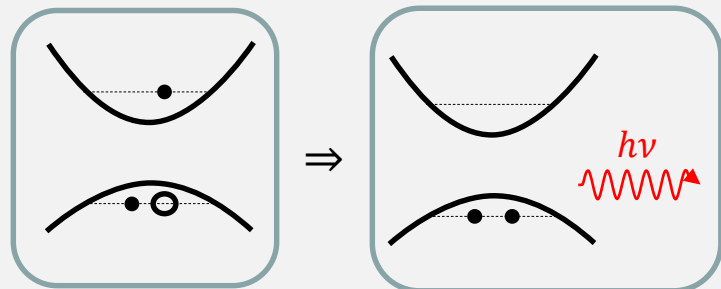


radiative processes in semiconductors

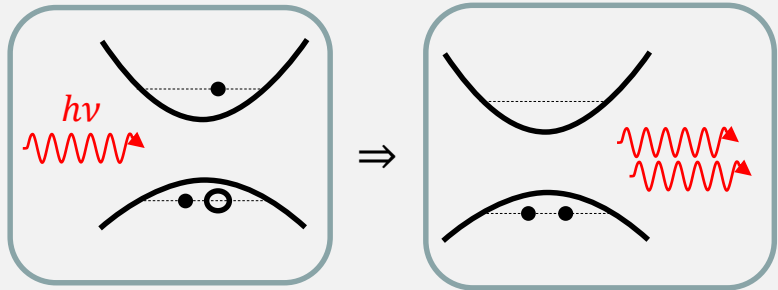
absorption



spontaneous emission



stimulated emission



conservation principles

for absorption:

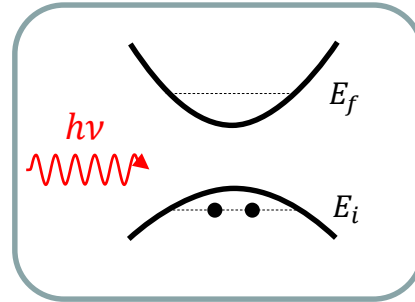
$$E_i + h\nu = E_f$$

$$\hbar\vec{k}_i + \hbar\vec{k}_p = \hbar\vec{k}_f$$

momentum
after absorption

momentum
before absorption

photon momentum



numbers:

electron $|\hbar\vec{k}_e| = \left| m_e^* \sqrt{\frac{3kT}{m_e^*}} \right| \approx 1,6 \cdot 10^{-26} \text{ kgm/s for GaAs}$

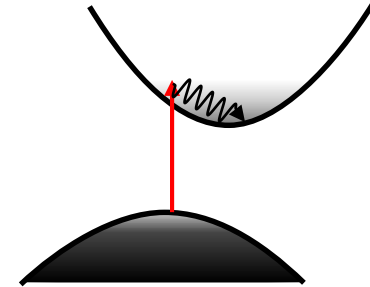
photon $|\hbar\vec{k}_p| = \frac{h}{\lambda} \approx 8 \cdot 10^{-28} \text{ kgm/s } (\lambda=800\text{nm})$

$$|\hbar\vec{k}_p| \ll |\hbar\vec{k}_i| \text{ and}$$

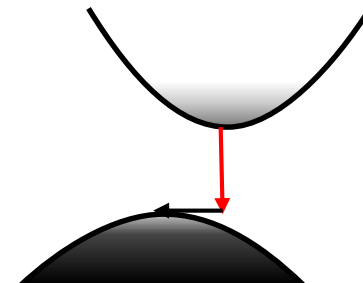
$$\vec{k}_f \cong \vec{k}_i$$

radiative transitions in semiconductor are „vertical“

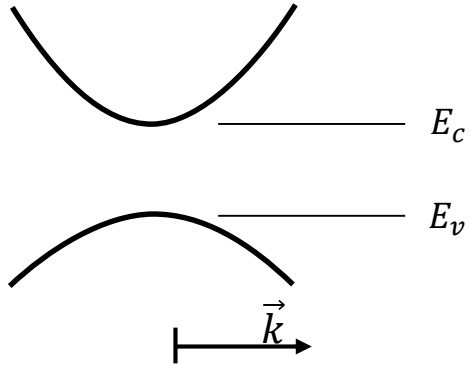
in semiconductors with indirect band gap, e.g. Si absorption is allowed. We can build very good photodetectors out of Si.



in semiconductors with indirect band gap radiative electron-hole recombination requires a photon to fulfill the momentum conservation rule. Thus radiative recombination has little probability – we cannot have light gain and thus build lasers.



differential density of electron states



Pauli's principle!

if we approximate the shape of the bands around $k = 0$ by parabolas then (no proof given here):

$$\varrho_c(E) = \frac{(2m_e^*)^{3/2}}{2\pi^2 \hbar^3} \sqrt{E - E_c}$$

$$\varrho_v(E) = \frac{(2m_h^*)^{3/2}}{2\pi^2 \hbar^3} \sqrt{E_v - E}$$

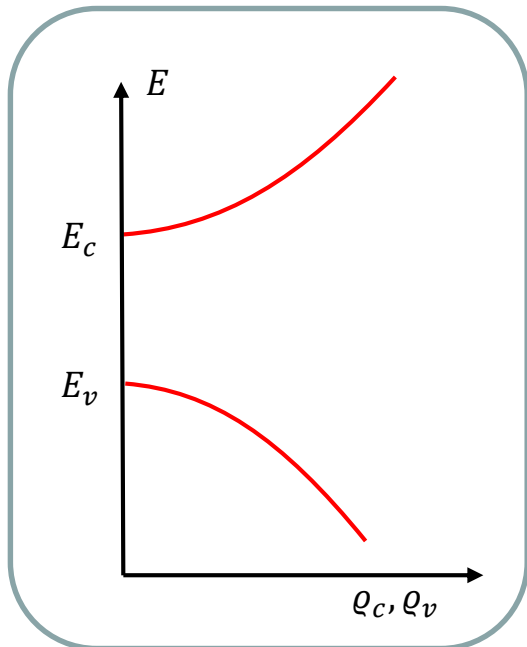
m_e^* electron effective mass

m_h^* hole effective mass

ϱ_v and ϱ_c have units $\frac{1}{\text{m}^3 \text{J}}$

interpretation:

- for given ΔE the product $\varrho_c(E)\Delta E$ is equal to maximum density of electrons with energy from $E - \Delta E/2 \div E + \Delta E/2$ range.
- the same applies to holes



Fermi's distribution

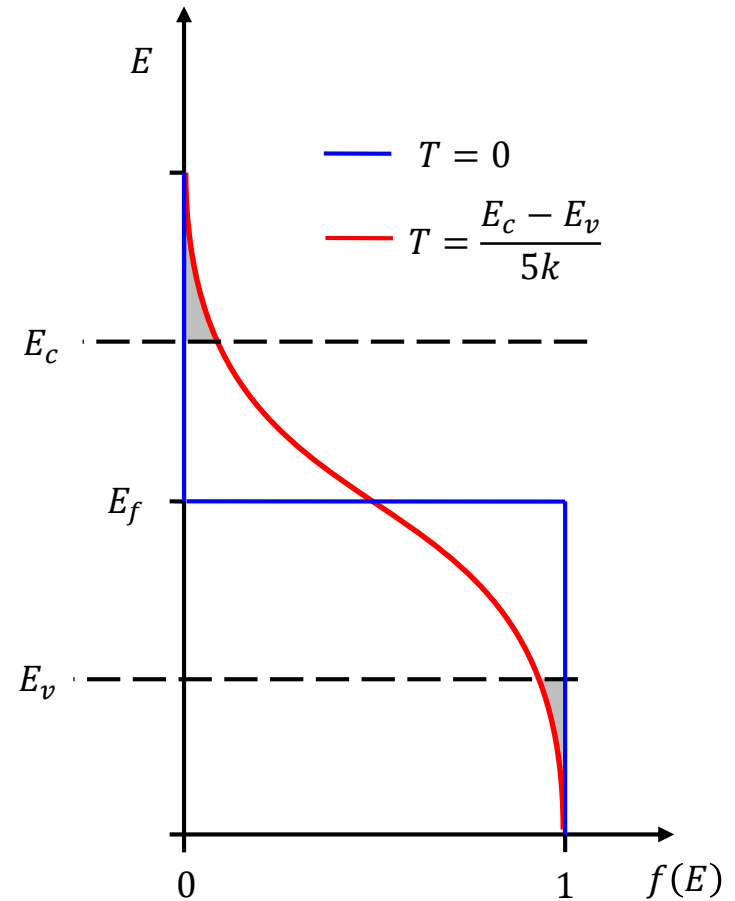
electrons are fermions

$$f(E) = \frac{1}{e^{\frac{E-E_f}{kT}} + 1}$$

E_f - Fermi's energy

T - temperature

k - Boltzman's constant



for $E > E_c$

for $E < E_v$

$f(E)$ - probability of finding an electron at a level with energy E

$1 - f(E)$ - probability of finding hole at a level with energy E

differential density of carriers

differential density of electrons – number of electrons in a unit volume (density) per unit energy band

$$n(E) = \rho_c(E)f(E) \quad \frac{1}{\text{m}^3\text{J}}$$

differential density of holes

$$p(E) = \rho_v(E)[1 - f(E)]$$

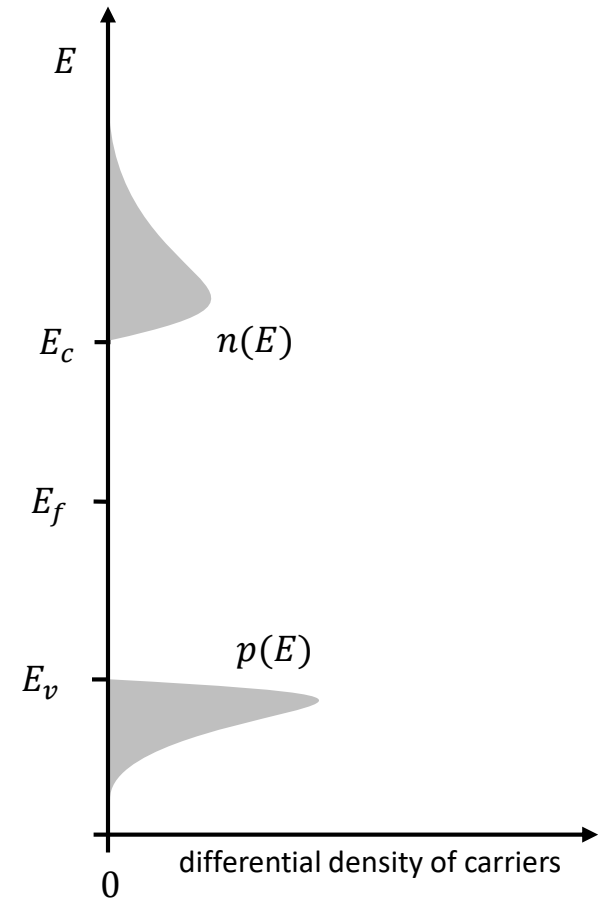
density of electrons

$$n = \int_{E_c}^{\infty} n(E)dE \quad \frac{1}{\text{m}^3}$$

density of holes

$$p = \int_{-\infty}^{E_v} p(E)dE$$

in a pure (no doping) semiconductor $n = p$.

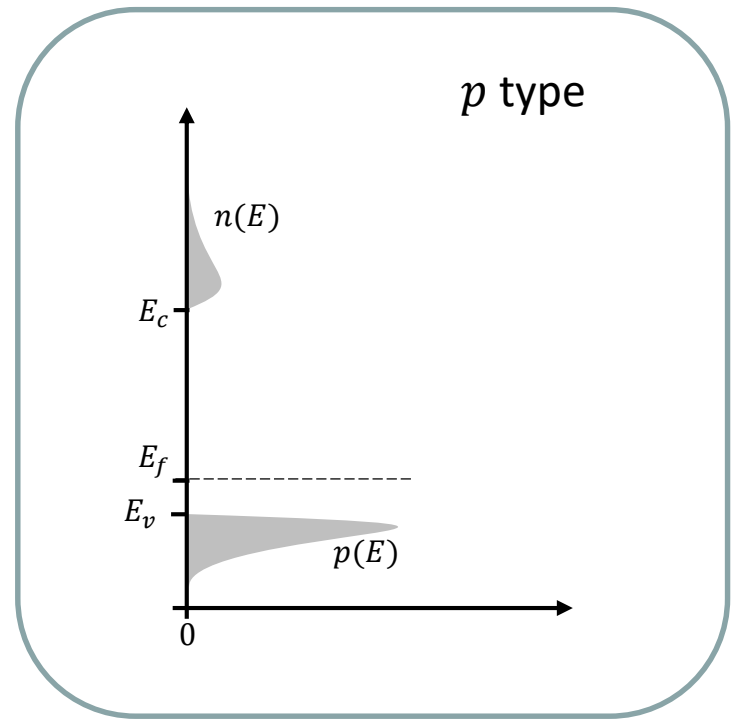
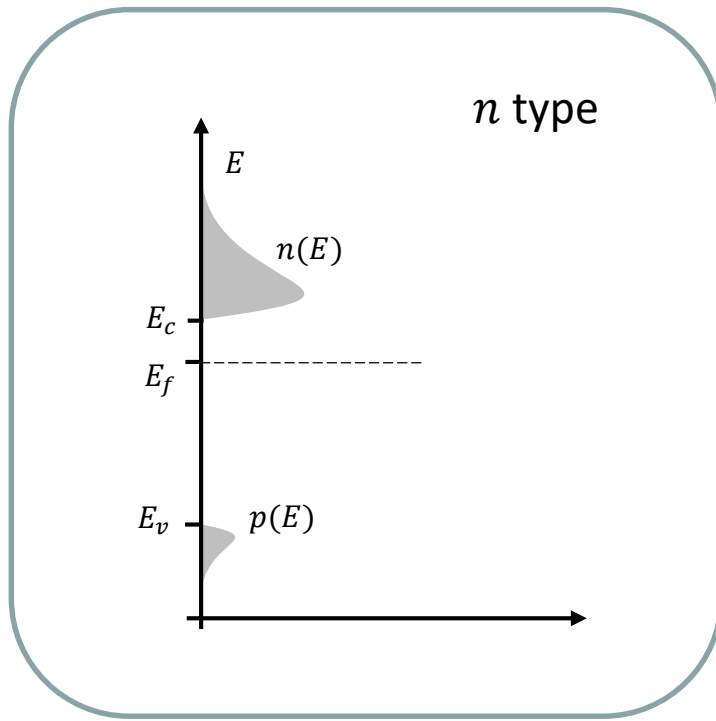


doped semiconductors

Two types of dopants: n (excessive number of electrons) and p (excessive number of holes)

$$n \neq p$$

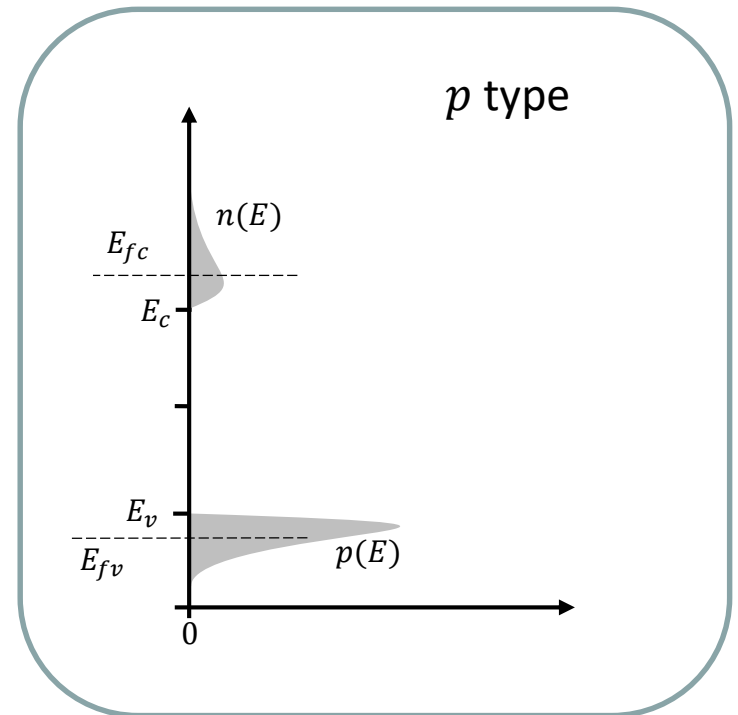
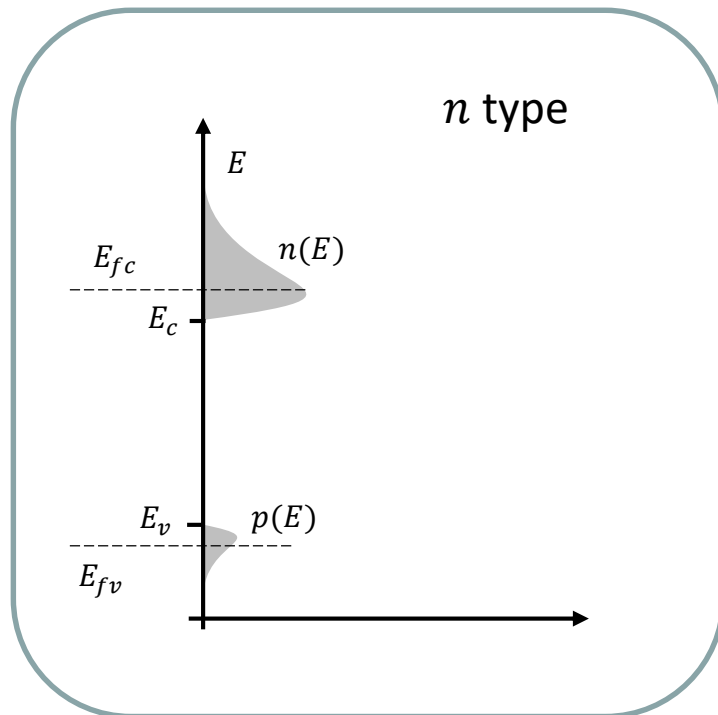
In doped semiconductors the Fermi's level is no longer half-way between valence and conduction bands.



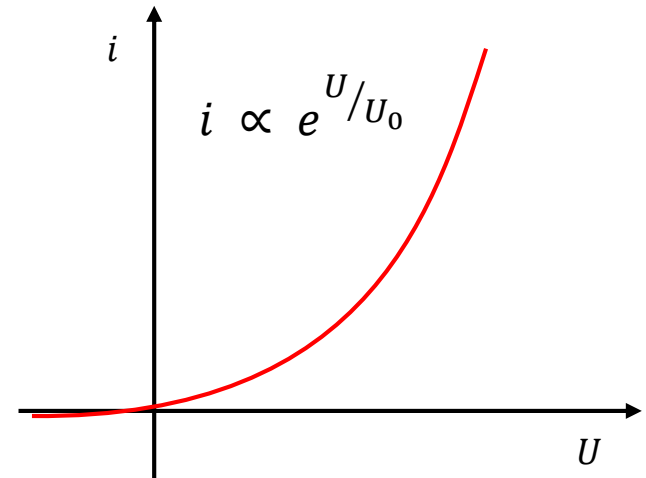
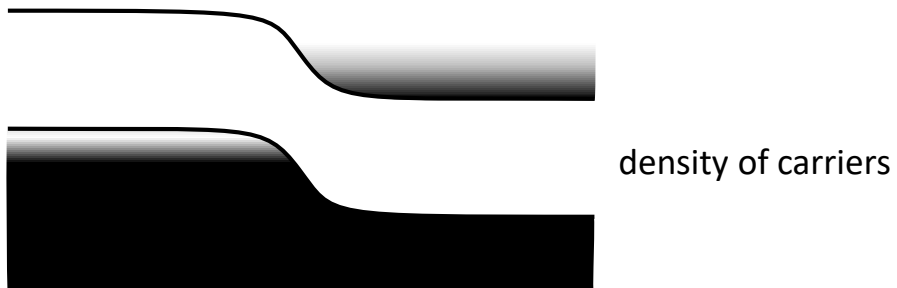
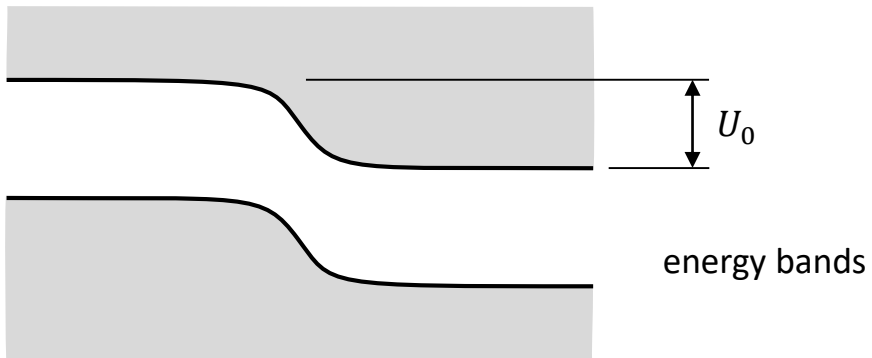
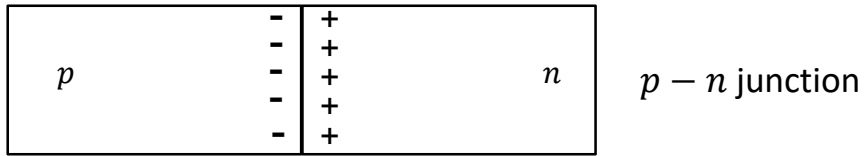
doped semiconductors with optical pumping or current injection

Two types of dopants: n (excessive number of electrons) and p (excessive number of holes) $n \neq p$

interband relaxation is much faster than the decay of electrons from the conduction band. Local thermodynamic equilibrium in any of the two bands is reached very quickly. We can define local Fermi's energies: E_{fv} and E_{fc}

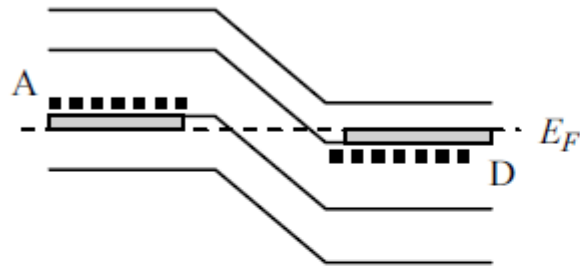


$p - n$ junction



p – n junction polarization

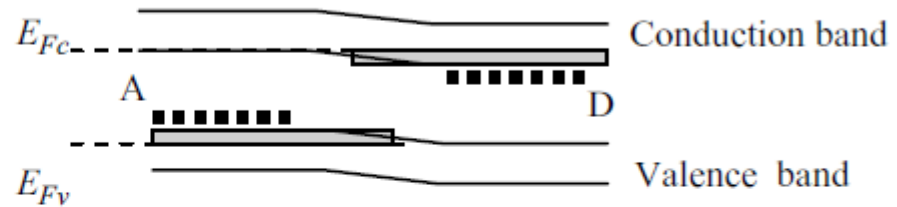
Without external voltage
no carriers at pn-junction



p-region

n-region

External voltage leads to
carrier injection at pn-junction




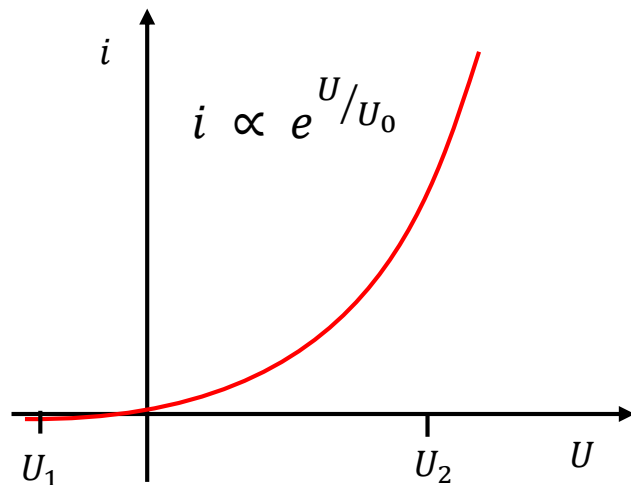
p-region

n-region

A Acceptor levels

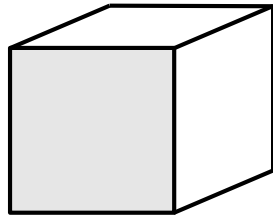
D Donator levels

 Region with free carriers

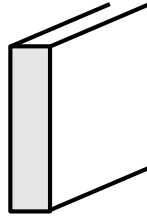


Both electrons and holes are present in the junction
– radiative recombination and thus gain are possible
photon energy \approx bandgap

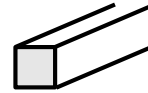
low-D structures



volume crystal
(3D)



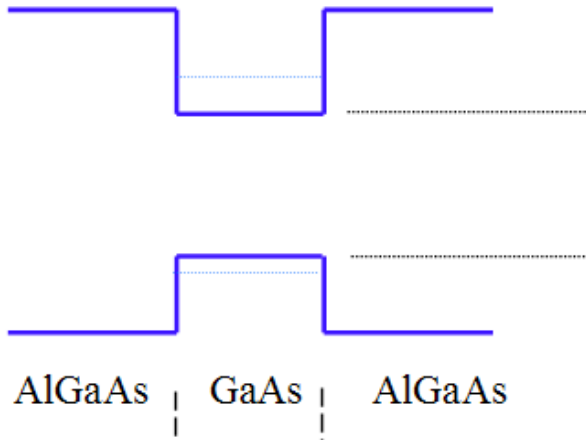
quantum well
(2D)



quantum wire
(1D)



quantum dot
(0D)

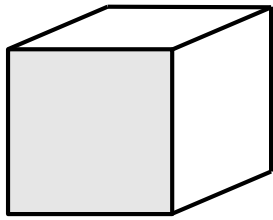


- In a quantum well the motion of electron along the direction normal to the well is quantized – energy levels corresponding to this motion are discrete.
- The number of bound levels depends on the width and depth of the well
- The total energy of the carrier is the sum of the energy of discrete levels and the Energy of free motion in the two directions parallel to the well.

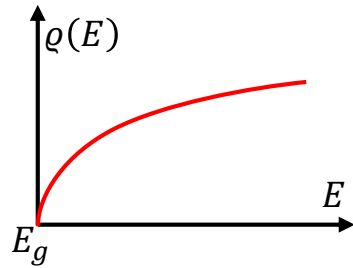
How can we build low-D structures? – semiconductor alloys

-
- For quantum dot all the energy levels are discrete

densities of electron states in low-D structures

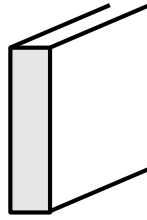


volume crystal
(3D)

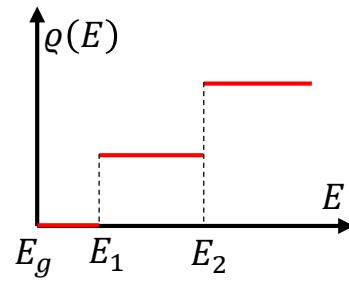


$$\varrho(k) = \frac{k^2}{2\pi^2}$$

$$\varrho(E) = \frac{(2m)^{3/2}}{2\pi^2 \hbar^3} \sqrt{E}$$

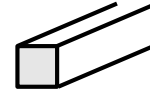


quantum well
(2D)

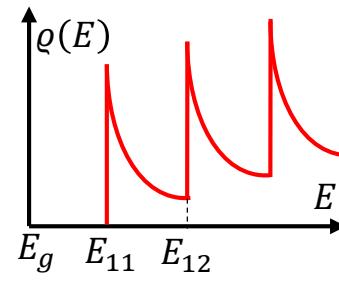


$$\varrho(k) = \frac{k}{2\pi} \left(\frac{1}{L_z} \right)$$

$$\varrho(E) = \frac{m}{2\pi \hbar^2} \frac{1}{L_z}$$



quantum wire
(1D)

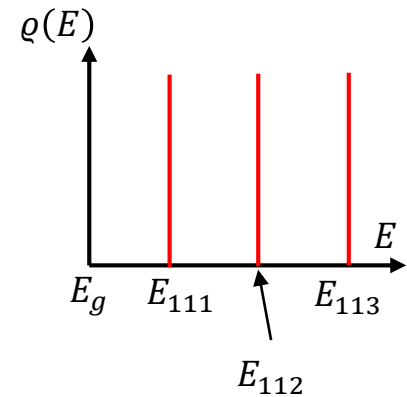


$$\varrho(k) = \frac{1}{\pi} \left(\frac{1}{L_x L_y} \right)$$

$$\varrho(E) = \frac{\varrho(k) \sqrt{2m}}{2\hbar} \frac{1}{\sqrt{E}}$$

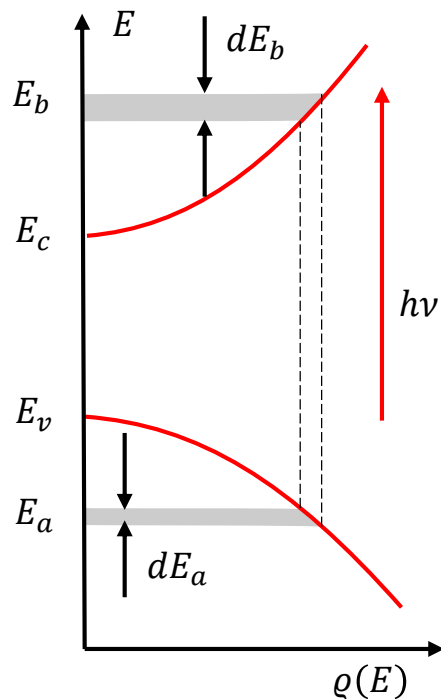


quantum dot
(0D)



$$\varrho(E) \propto \delta(E - E_{ikl})$$

gain lineshape



bulk (3D)

momentum conservation

$$\sqrt{2m_e^*(E_b - E_c)} = \sqrt{2m_h^*(E_v - E_a)}$$

gives

$$E_b - E_c = \frac{m_h^*}{m_e^*} (E_v - E_a)$$

and

$$dE_b = -\frac{m_h^*}{m_e^*} dE_a$$

calculations ...

give reduced density of states

$$\varrho_r(\nu) = \frac{1}{4\pi^2} \left(\frac{2m_r}{\hbar^2} \right)^{3/2} \sqrt{h\nu - E_g}$$

calculations ...

$$\begin{aligned} \gamma(\nu) &= B_{21} \frac{n}{c} \varrho_r(\nu) [f_c(E_b) - f_v(E_a)] = \\ &= \alpha_0(\nu) [f_c(E_b) - f_v(E_a)] \end{aligned}$$

absorption lineshape at $T = 0$.

$$0 \leq f_c, f_v \leq 1$$

the gain is possible only when $f_c(E_b) > f_v(E_a)$

this is an analogue of the population inversion ($\Delta N > 0$) in atoms/ions.

We need both types of carriers: electrons and holes to be present. This is consistent with the stimulated emission picture – in order to produce extra photon the hole and electron have to be annihilated.

gain lineshape, 2

low-D materials

- different formulas for reduced density of states, still the result is proportional to the densities of carriers
- result: higher densities of states leads to higher gain.

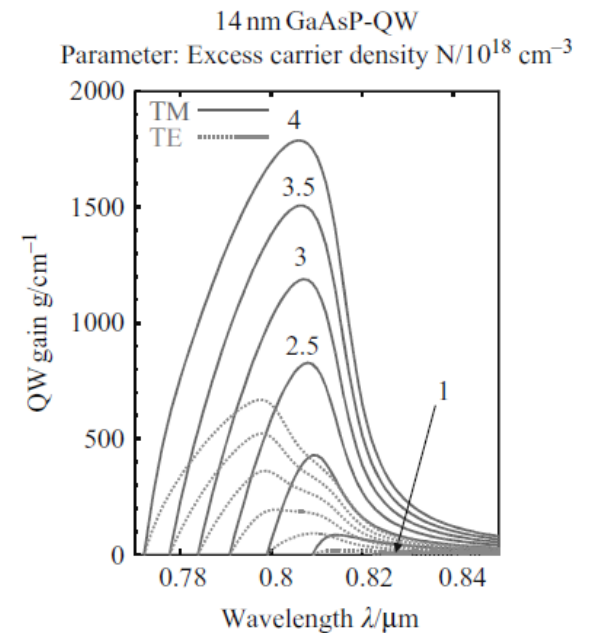
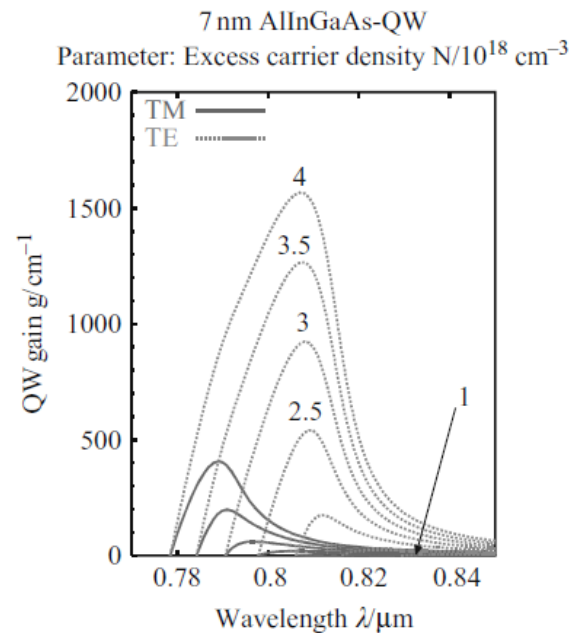


FIGURE 2.6. Calculated optical gain versus wavelength at different excitation levels for a compressively strained AlInGaAs-QW and a tensile-strained GaAsP-QW at 810 nm

semiconductor alloys

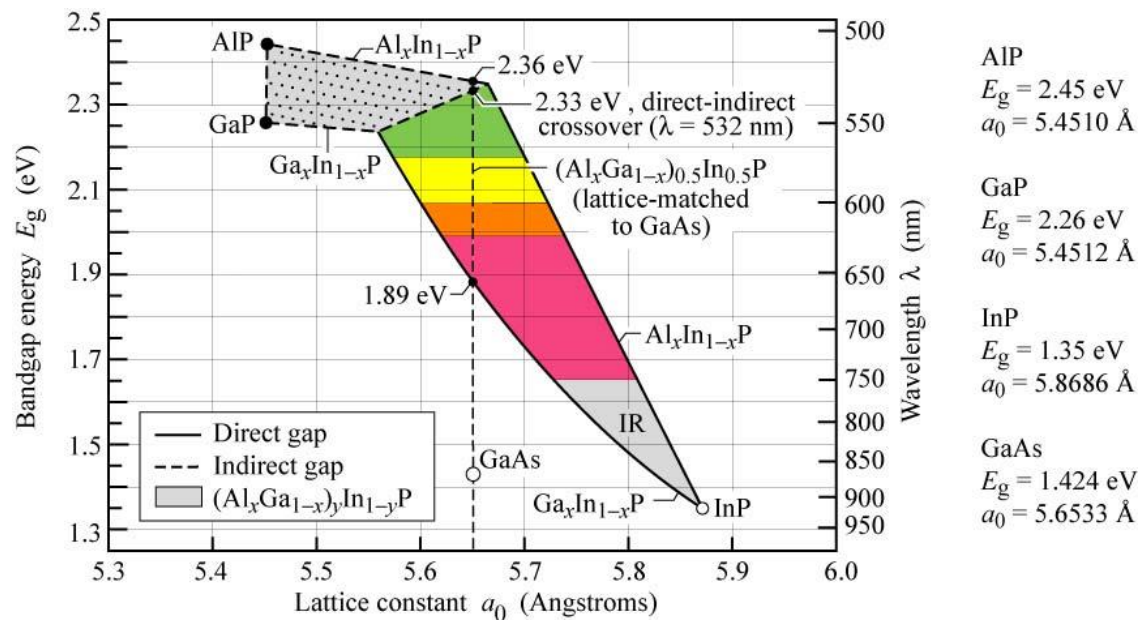


Fig. 12.9. Bandgap energy and corresponding wavelength versus lattice constant of $(\text{Al}_x\text{Ga}_{1-x})_y\text{In}_{1-y}\text{P}$ at 300 K. The dashed vertical line shows $(\text{Al}_x\text{Ga}_{1-x})_{0.5}\text{In}_{0.5}\text{P}$ lattice matched to GaAs (adopted from Chen *et al.*, 1997).

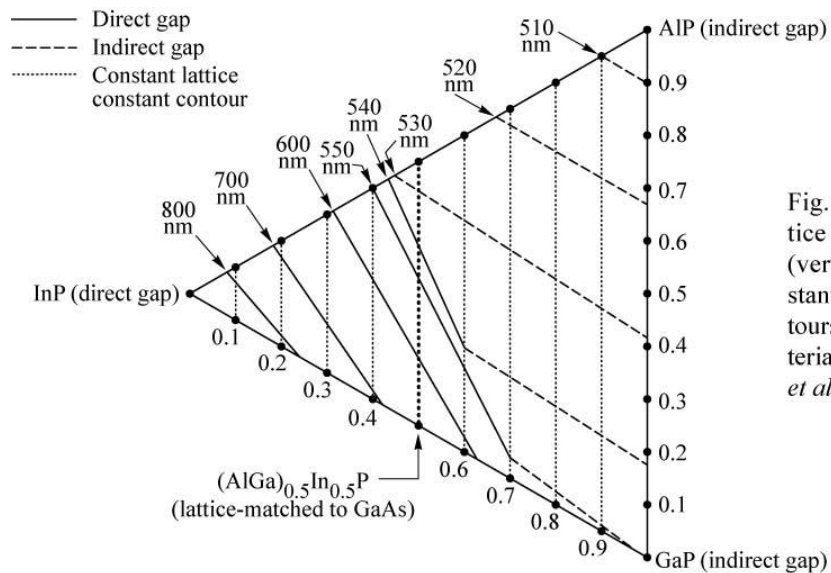


Fig. 12.11. Constant lattice constant contours (vertical lines) and constant emission line contours of the AlGaInP materials system (after Chen *et al.*, 1997).

semiconductor alloys, 2

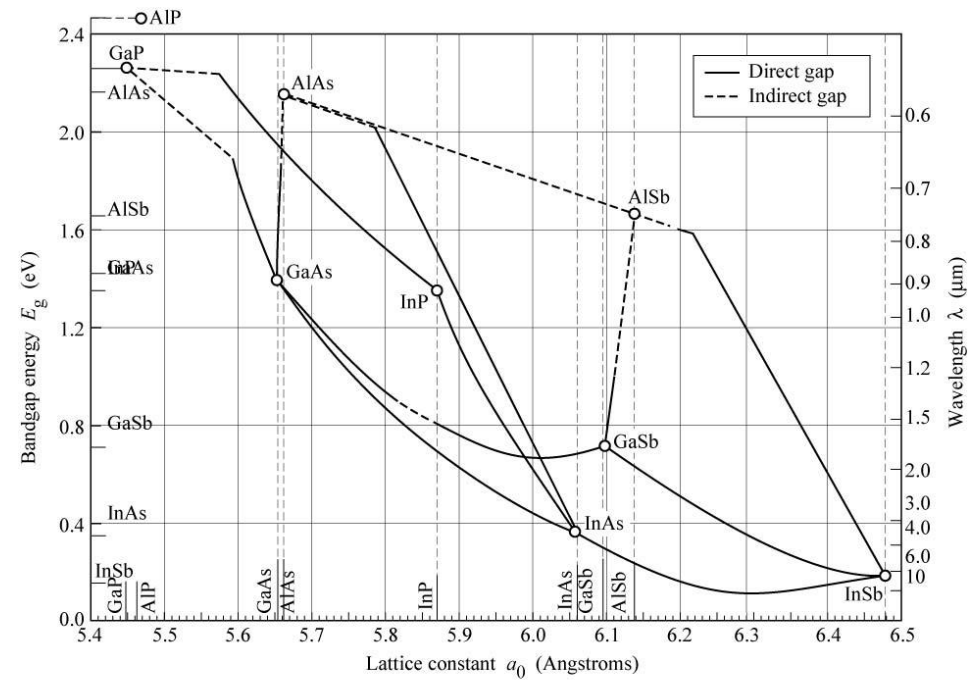
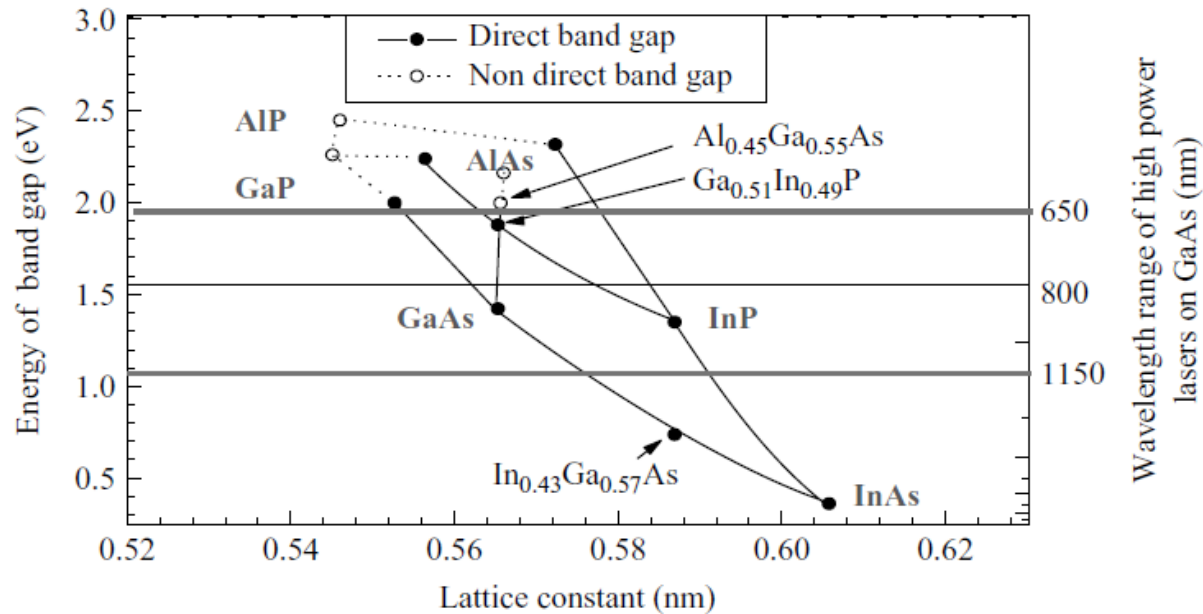


Fig. 12.6. Bandgap energy and lattice constant of various III-V semiconductors at room temperature (adopted from Tien, 1988).



Light Emitting Diode (LED)

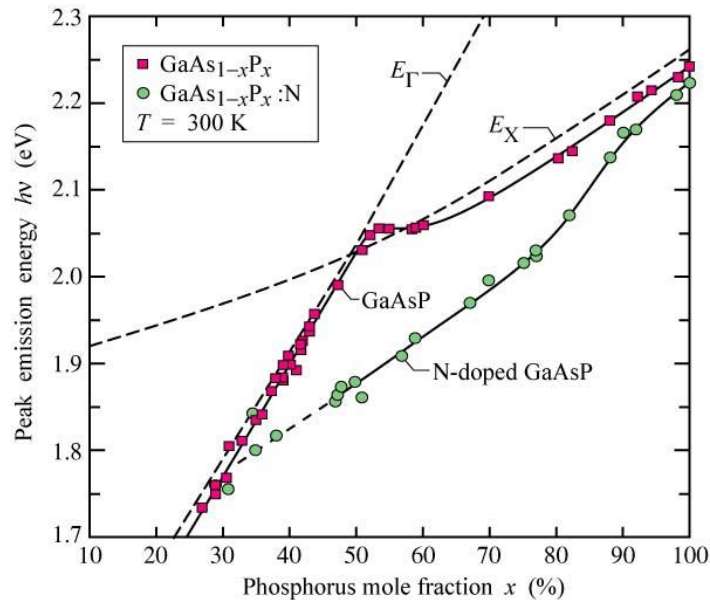


Fig. 12.2. Room-temperature peak emission energy versus alloy composition for undoped and nitrogen-doped GaAsP LEDs injected with a current density of 5 A/cm^2 . Also shown is the energy gap of the direct-to-indirect (E_{Γ} -to- E_X) transition. The direct-indirect crossover occurs at $x \approx 50\%$ (after Craford *et al.*, 1972).

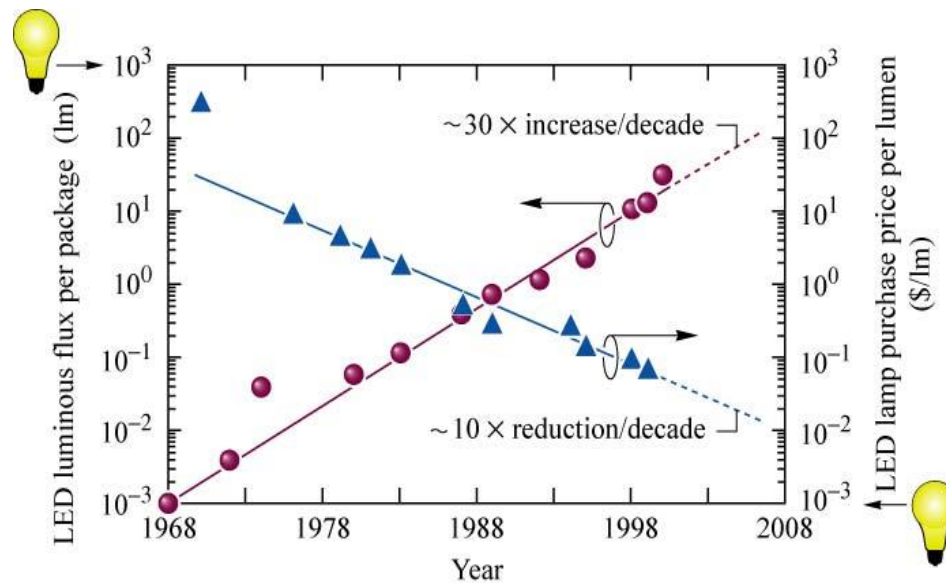


Fig. 12.15. LED luminous flux per package and LED lamp purchase price per lumen versus year. Also shown are the values for a 60 W incandescent tungsten-filament light bulb with a luminous efficiency of $\sim 17 \text{ lm/W}$ and a luminous flux of 1000 lm with an approximate price of 1.00 US\$ (after Krames *et al.*, 2000).

laser cavities for semiconductor lasers

Two major groups:

1. edge emitting lasers, Fresnel reflections of the surfaces that form flat mirrors, eventually Bragg advantage: large powers possible disadvantage : strongly astigmatic output beam

Note that the vertical dimensions of the structures are, typically, μm

2. surface emitting lasers, Bragg mirrors are grown using MBE disadvantage: low powers advantage: high beam quality, large 2D matrices can be grown on a single wafer

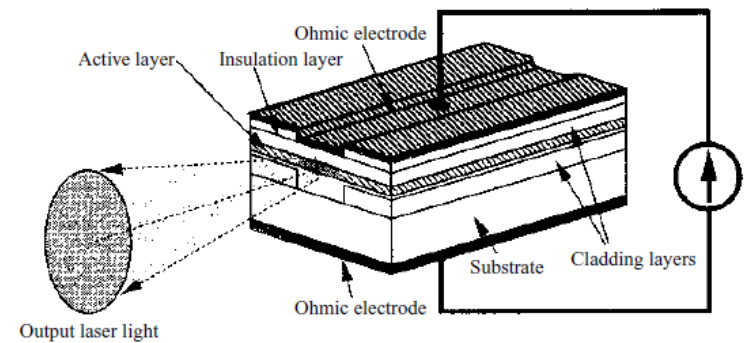
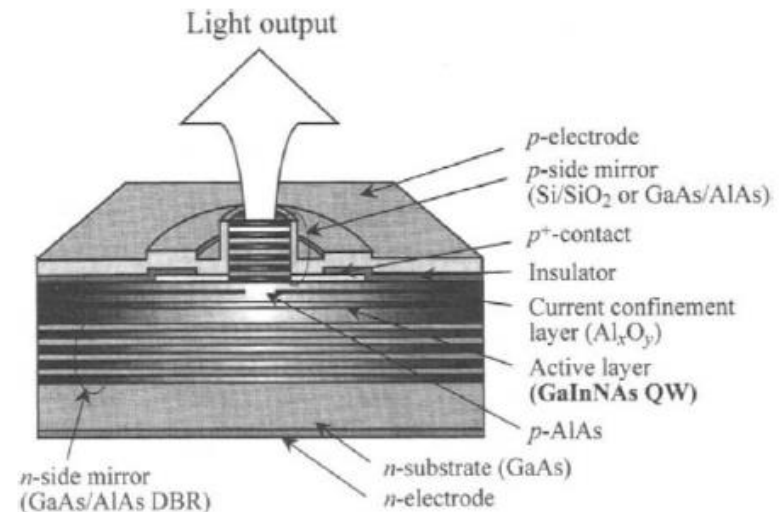
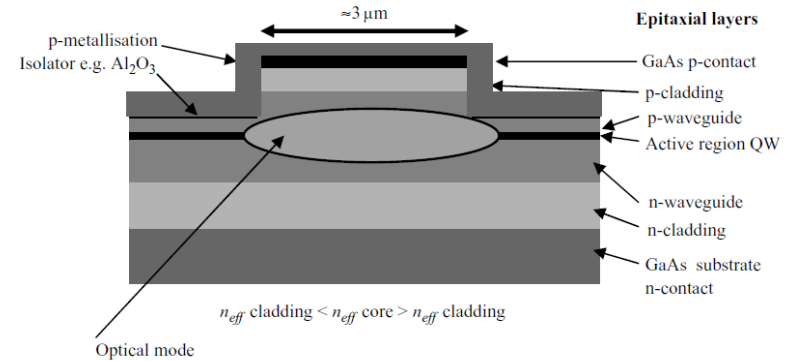


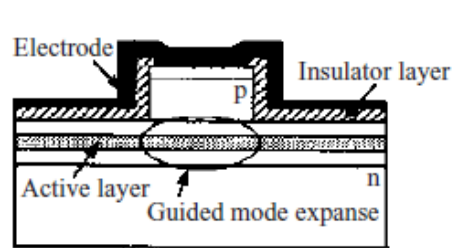
Figure 6.1 Schematic illustration of a double-heterostructure (DH) FP semiconductor laser.



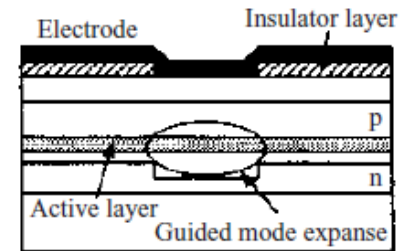
laser resonators for edge emitting lasers

Two methods for creating waveguides:

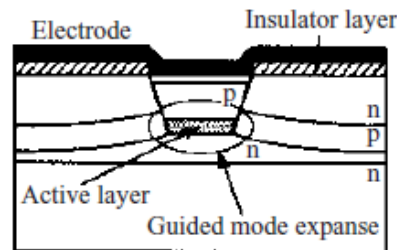
1. index guiding – the structure of the laser chip forms a waveguide which, together with end mirrors form a resonator



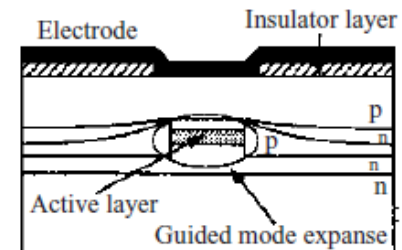
Ridge waveguide type



Rib waveguide type



Buried heterostructure waveguide type



2. gain guiding – the waveguide does not exist without pumping, the shape of the gain region guides some waves by providing them with the gain larger than for other (nonguided) waves.

narrowband and tuned semiconductor lasers

1. The tuning components (1D Bragg grating) is formed next to gain region on the laser chip.

optical telecommunications!!!

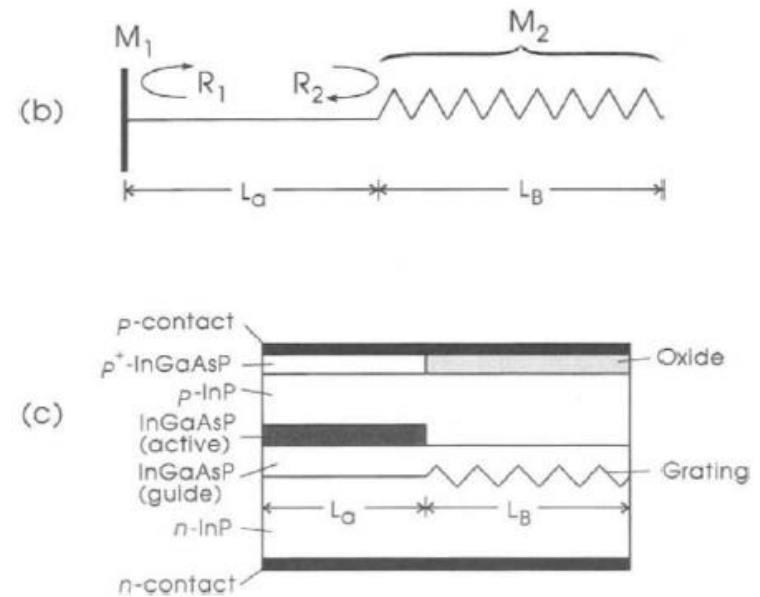
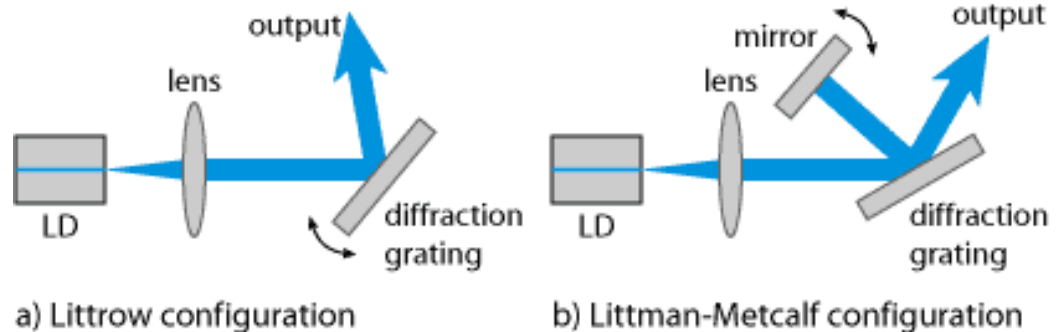
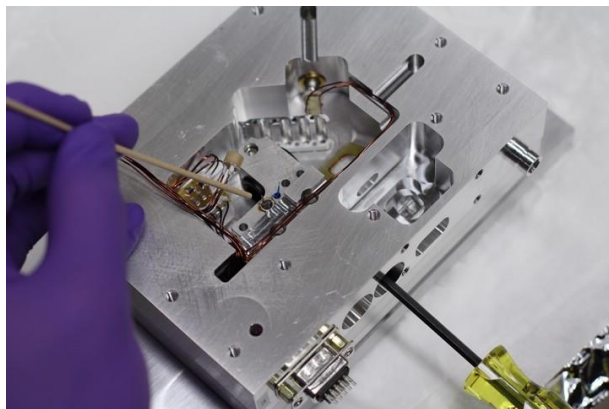
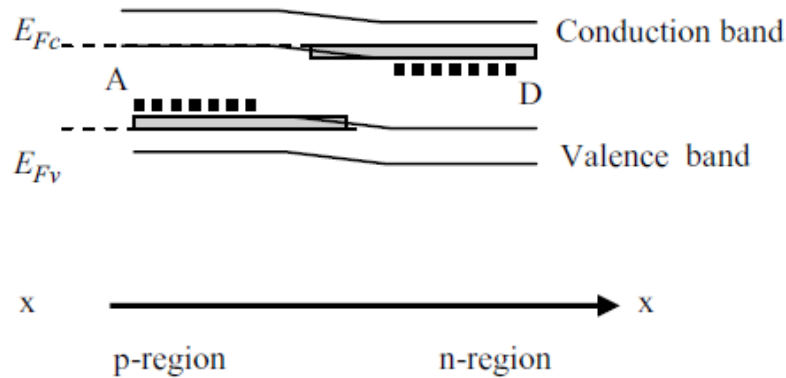


Figure 3.8: Distributed Bragg reflector (DBR) laser: (a) Both mirrors replaced by Bragg gratings. (b) One mirror replaced by a Bragg grating. (c) Schematic longitudinal view of InGaAsP/InP DBR laser.

2. External cavity line narrowing and tuning



$n - p$ junction lasers

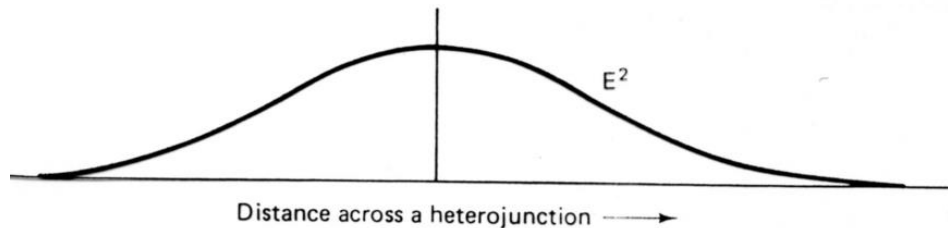
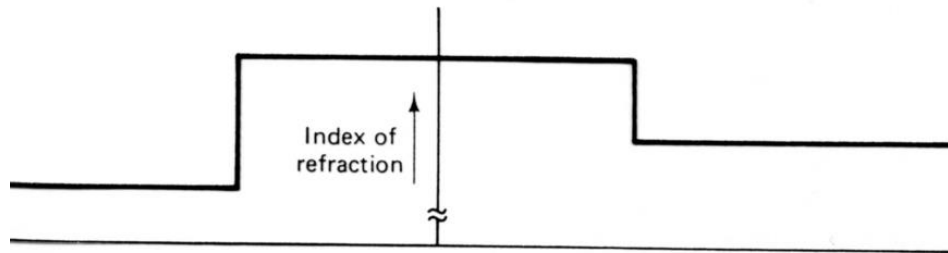
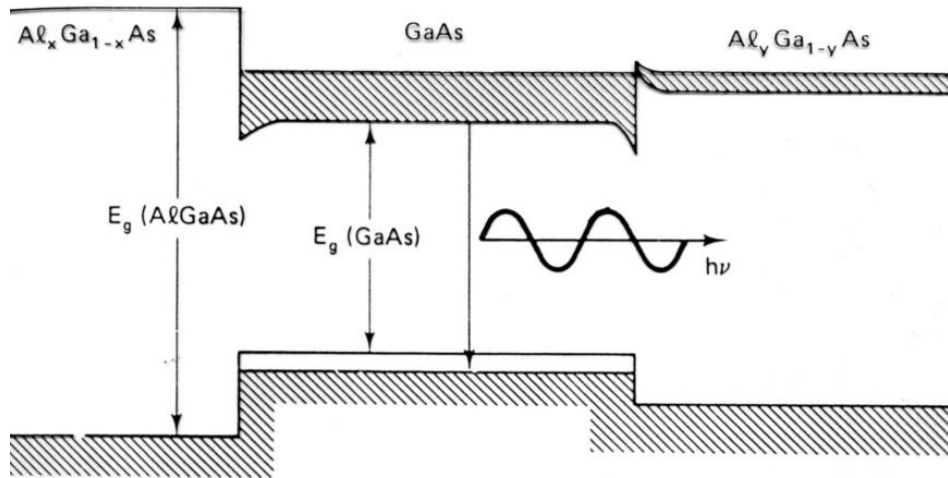


Historical value only.

If we apply voltage in the conduction direction a current will flow through the junction the band structure will be deformed in such a way that both types of carriers can be present in the junction at the same time (condition for gain).

Because of the carriers diffusion those lasers required very high currents, typically $>10\text{kA/cm}^2$ which results in very strong heating.

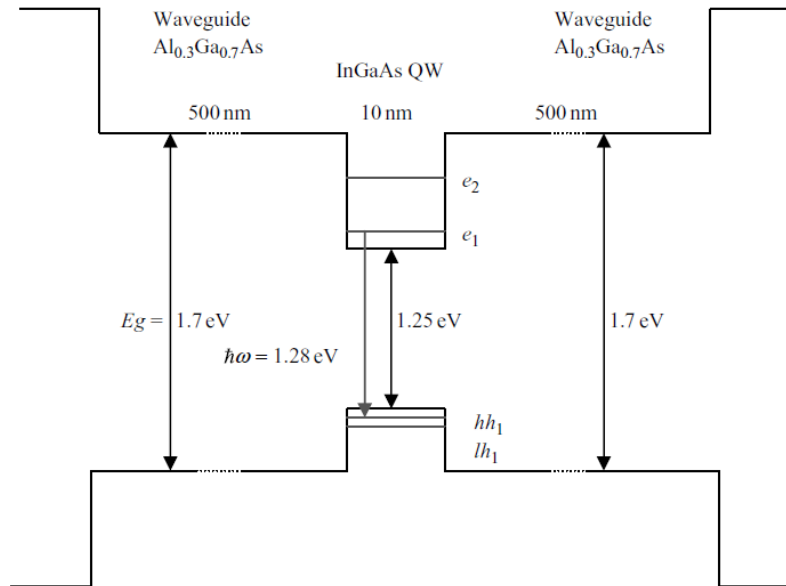
double heterojunction structure lasers



The heterojunction plays two roles

1. Carrier trapping – the electrons and holes are trapped in the potential minima which facilitates radiative recombination and by many orders of magnitude lowers the electrical current required
2. Different materials with different indices of refraction form a waveguide.

quantum well semiconductor lasers

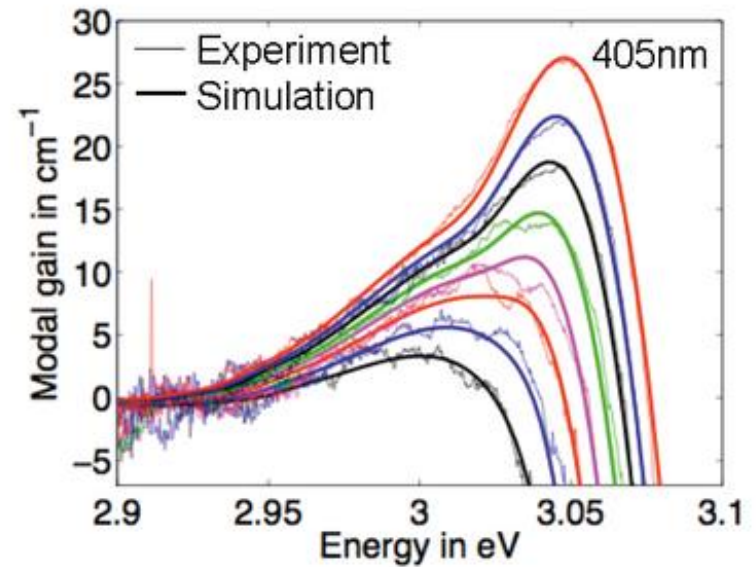
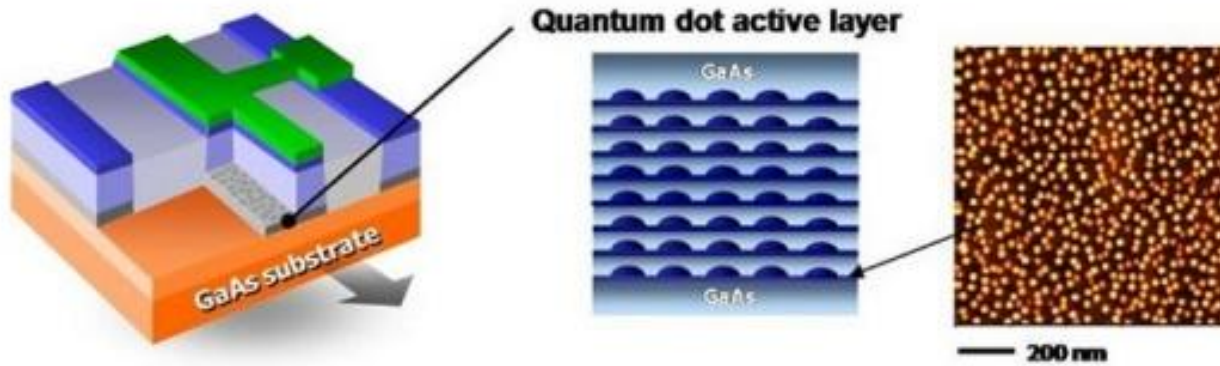


An example:

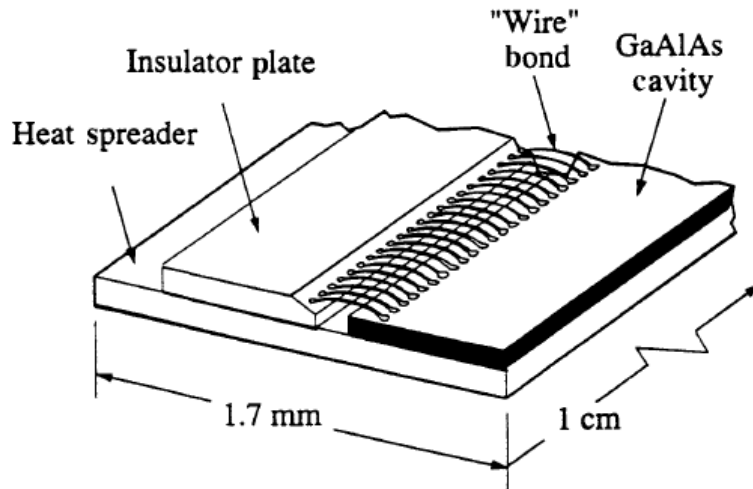
gain medium 10nm InGaAs quantum well

waveguide – double heterojunction

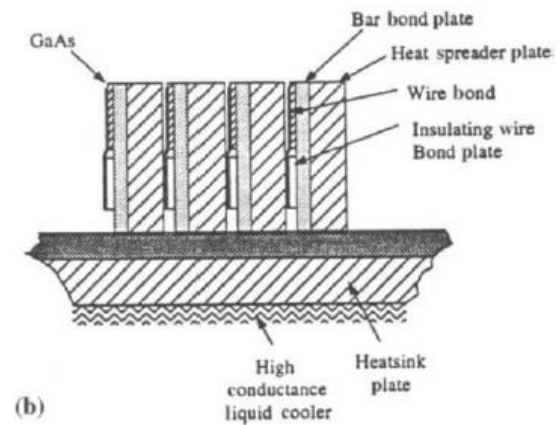
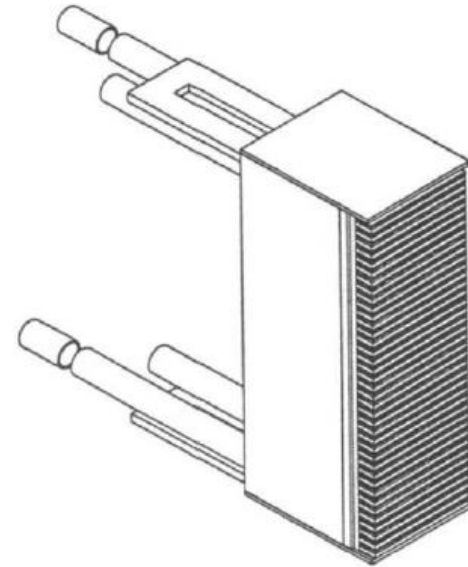
quantum dot semiconductor lasers



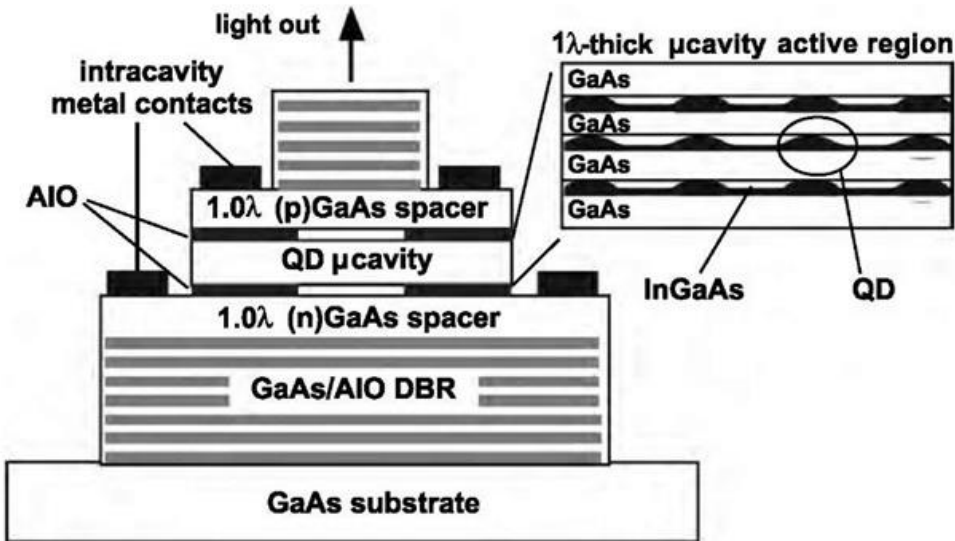
laser diode bar



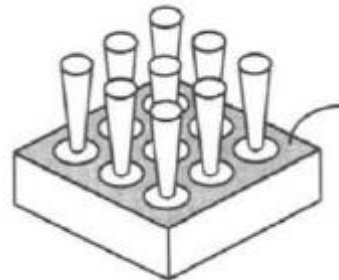
The power of a single diode laser is limited mostly by the limited ability to remove heat. Higher powers are achieved by stacking many chips and providing efficient cooling to each individual laser.



Vertical Cavity Surface Emitting Laser (VCSEL)



- excellent beam quality (TEM_{00})
- easy to run in a single mode regime



VCSEL laser matrices

Wavelength (μm)	0.3	0.5	0.8	1.0	1.3	1.5
GaInAsP/InP AlGaInAs/InP					<u>1.3~1.5</u>	
GaInNAs/GaAs					<u>1.3</u>	
GaInAs/GaAs				<u>0.98</u>		
GaAlAs/GaAs			<u>0.78~0.88</u>			
GaAlInP/GaAs		<u>0.63~0.67</u>				
ZnSSe/ZnMgSSe		<u>0.45~0.5</u>				
GaInAlN/GaAlN	<u>0.3~0.5</u>					

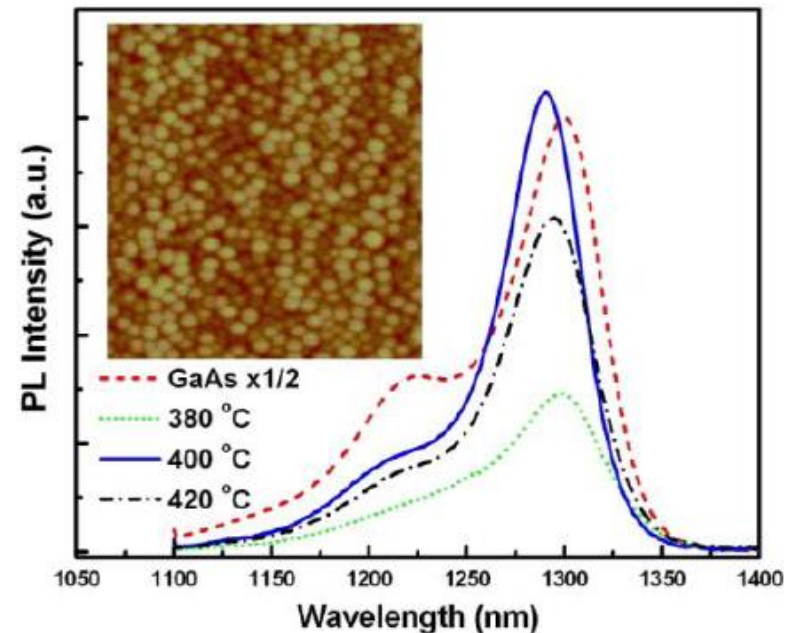
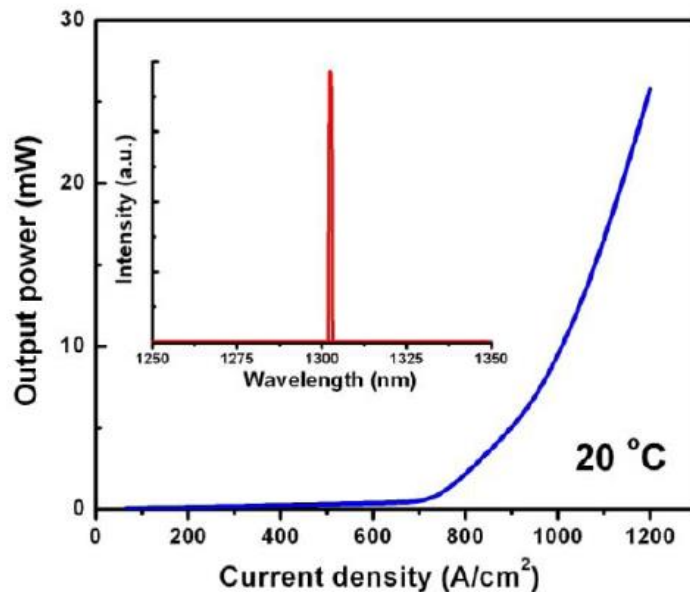
50nm GaAs	x2
100nm Al _{0.4} Ga _{0.6} As	
50nm GaAs	
5 layer InAs/InGaAs DWELL	
50nm GaAs	
100 layer GaAs/AlGaAs SPLs	
400nm GaAs	
5 layer In _{0.15} Ga _{0.85} As/GaAs SPLs	
1 μ m GaAs	
Si Substrate	

Dilemma: silicon electronics dominates but one cannot build a laser with a silicon crystal because it has indirect gap.

1.3- μ m InAs/GaAs quantum-dot lasers monolithically grown on Si substrates

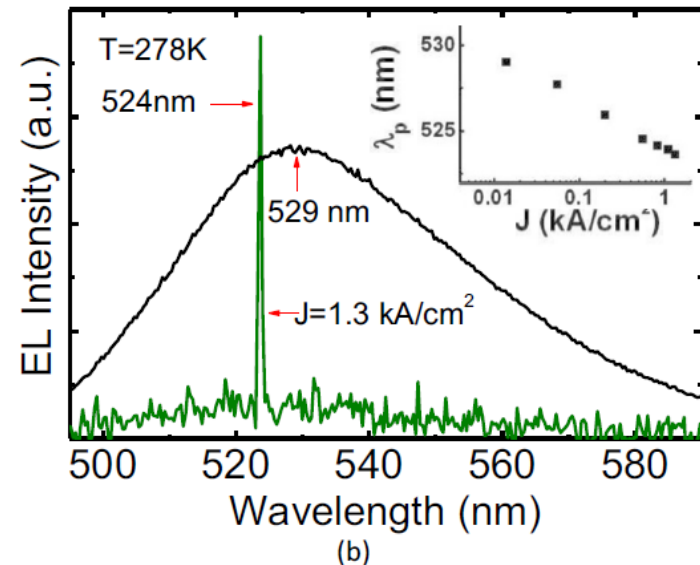
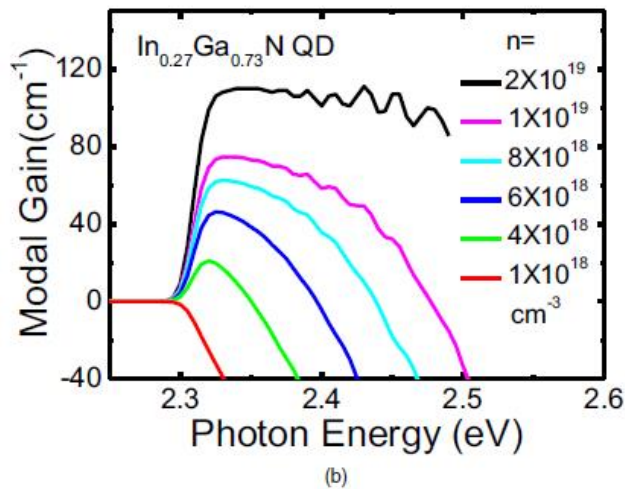
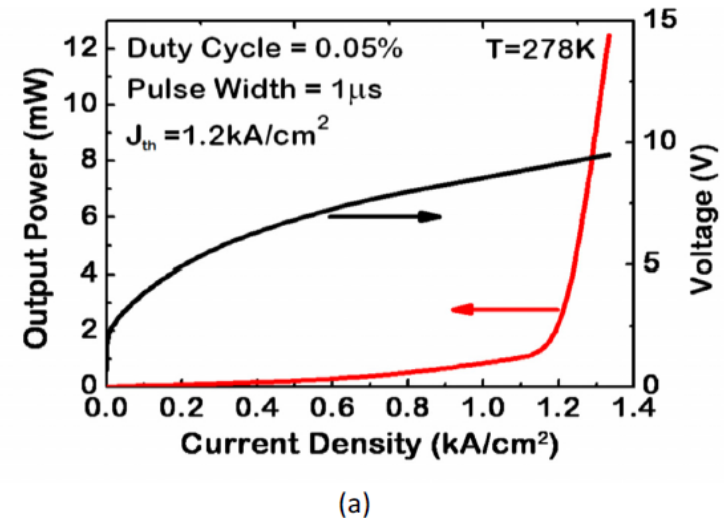
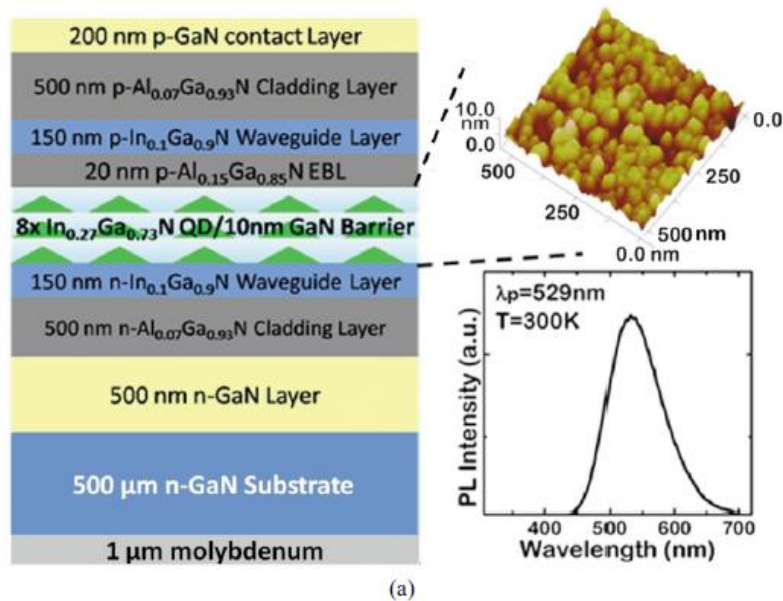
Ting Wang, Huiyun Liu,* Andrew Lee, Francesca Pozzi, and Alwyn Seeds

6 June 2011 / Vol. 19, No. 12 / OPTICS EXPRESS 11381

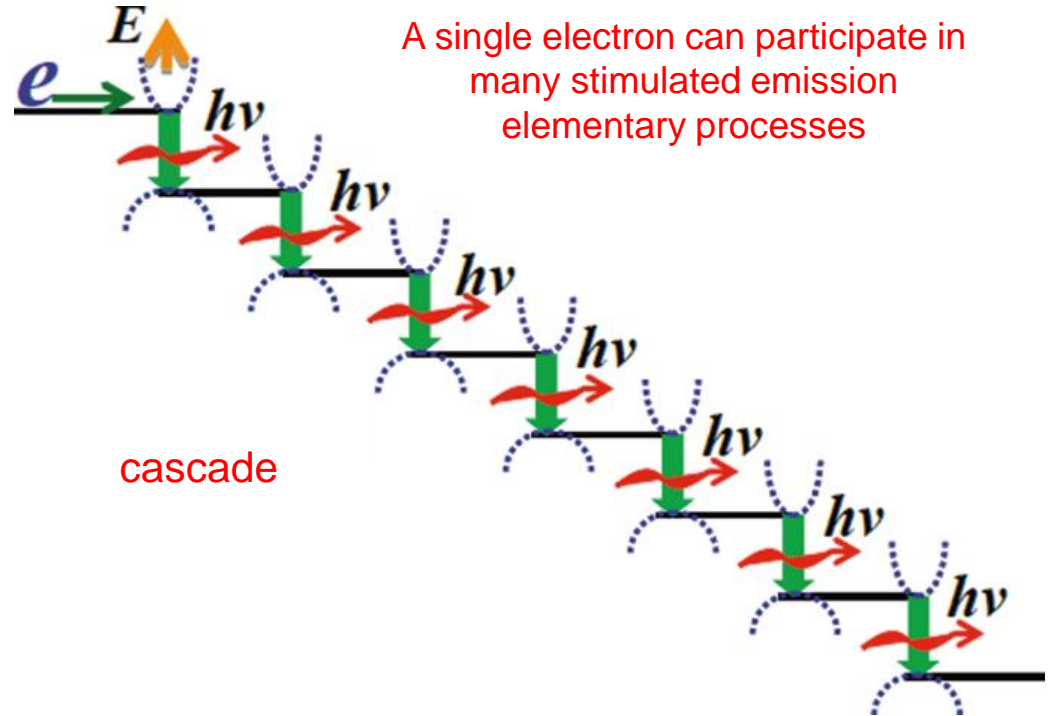
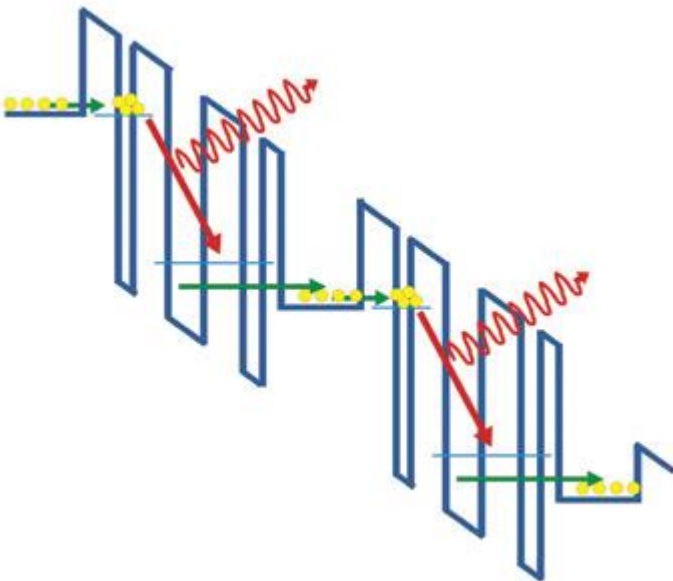
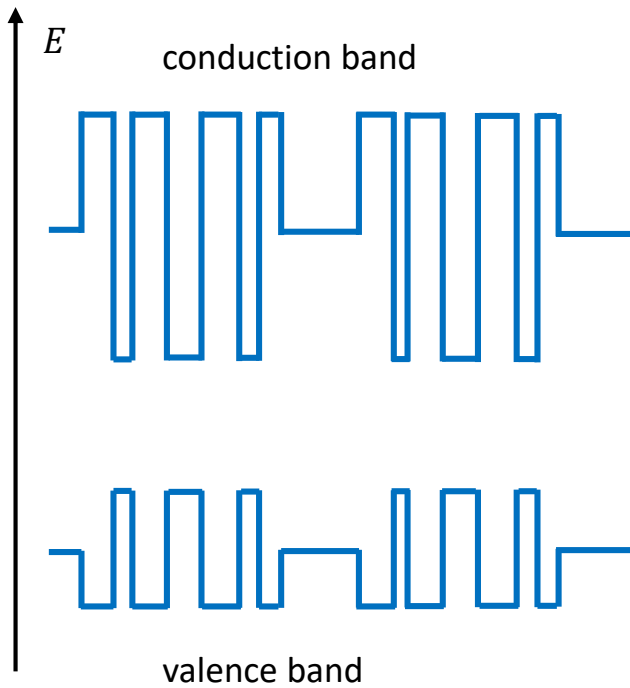


A InGaN/GaN quantum dot green ($\lambda=524$ nm) laser

Meng Zhang, Animesh Banerjee, Chi-Sen Lee, John M. Hinckley, and Pallab Bhattacharya^{a)}

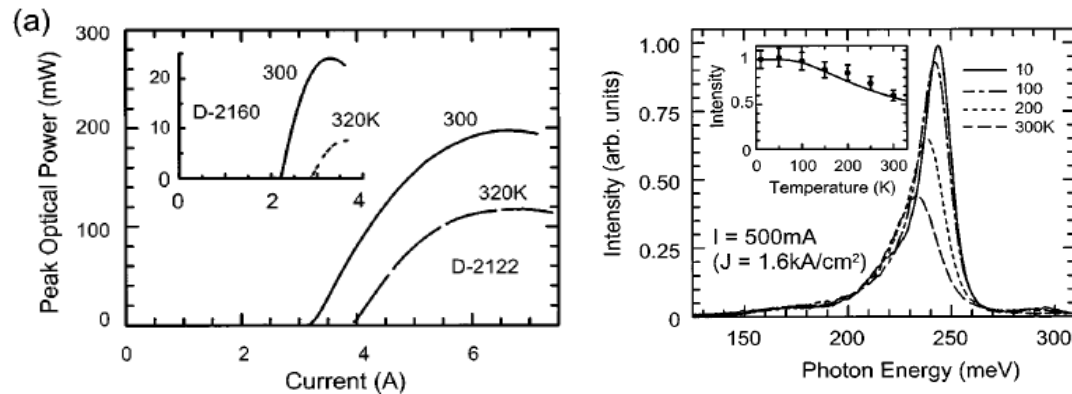
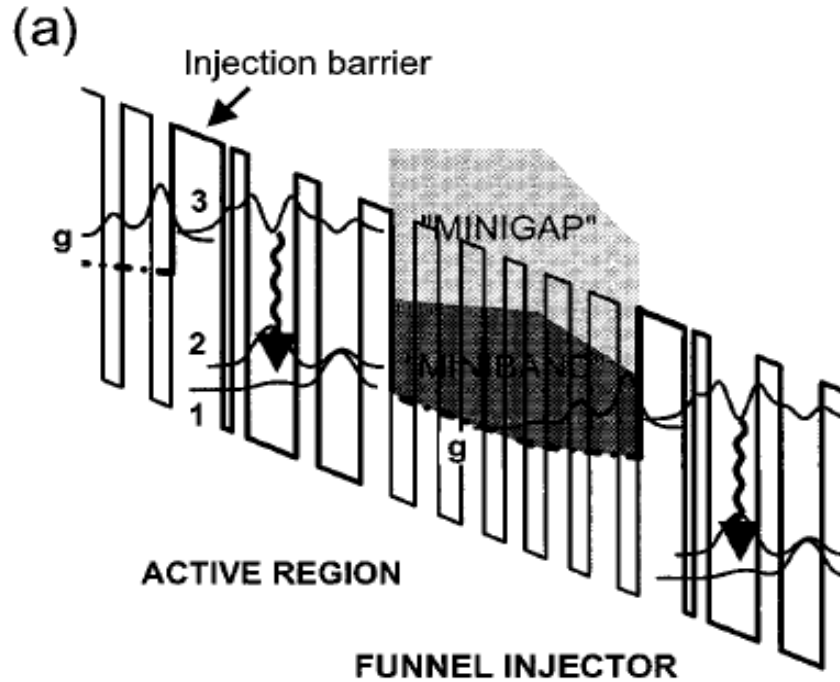


quantum cascade laser



quantum cascade laser, 2

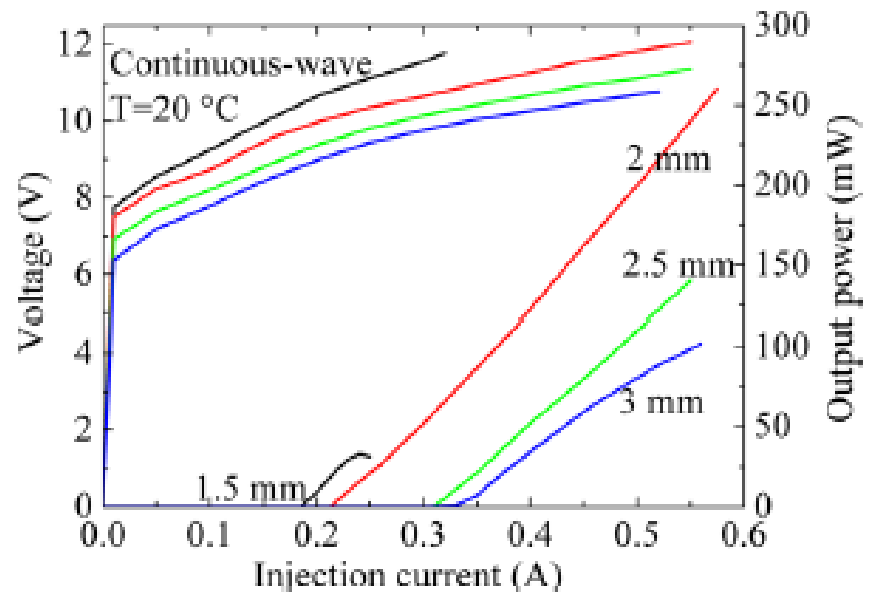
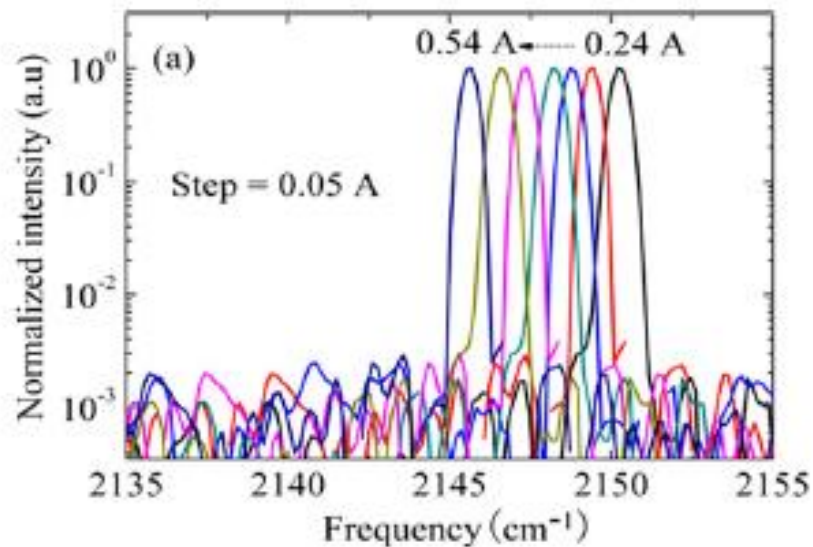
Appl. Phys. Lett. **68** (26), 24 June 1996



High-performance uncooled distributed-feedback quantum cascade laser without lateral regrowth

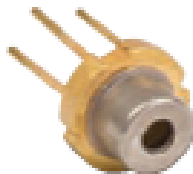
J. C. Zhang,^{1,2} F. Q. Liu,^{1,a)} S. Tan,¹ D. Y. Yao,¹ L. J. Wang,^{1,b)} L. Li,¹ J. Q. Liu,¹
and Z. G. Wang¹

APPLIED PHYSICS LETTERS **100**, 112105 (2012)



UV semiconductor lasers

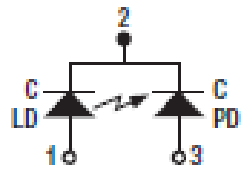
$\lambda = 375\text{ nm}$, $P = 20\text{ mW}$, Single Mode Thorlabs L375P020MLD



- Ø5.6 mm Package
- 20 mW (Typical) Optical Output Power (CW)
- 1.2 W/A (Typical) Slope Efficiency

S05LM9 Included

Pin Description
1 laser anode
2 common case (cathode)
3 monitor diode anode



PIN CODE B

NEW
product

ITEM #	\$	£	€	RMB	DESCRIPTION
L375P020MLD*	CALL	CALL	CALL	CALL	Thorlabs 375 nm, 20 mW

*Ships with S05LM9, an SM05-compatible mount for Ø5.6 mm and Ø9 mm packages

Maximum Ratings ($T_c = 25\text{ }^\circ\text{C}$)

CHARACTERISTIC	SYMBOL	MAX RATING
Optical Output Power (CW)	P_o	30 mW*
LD Reverse Voltage	$V_{R(LD)}$	5 V
PD Reverse Voltage	$V_{R(PD)}$	20 V
Operation Case Temperature	T_{op}	20 to 30 $^\circ\text{C}$
Storage Temperature	T_{stg}	-40 to 85 $^\circ\text{C}$

*20 mW Typical

Characteristics ($T_c = 25\text{ }^\circ\text{C}$, $P = 20\text{ mW}$)

CHARACTERISTIC	SYMBOL	MIN	TYP	MAX
Lasing Wavelength	λ_p	370 nm	375 nm	380 nm
Threshold Current	I_{th}	—	45 mA	60 mA
Operating Current	I_{op}	—	60 mA	85 mA
Operating Voltage	V_{op}	4.5 V	5.2 V	6.5 V
Beam Divergence (FWHM)	$\theta_{//}$	5°	8.5°	13°
	θ_{\perp}	18°	22°	26°
Slope Efficiency	η_s	0.9 mW/mA	1.2 mW/mA	1.6 mW/mA
Monitor Current	I_m	—	0.2 mA	—

Note: All data are presented as typical unless otherwise specified.

Laser Diode Modules

Tunable Lasers

Femtosecond Lasers

Optical Amplifiers

405 nm Pigtailed Laser Diode



Available with Single Mode Fiber

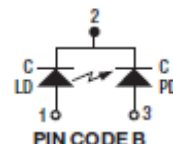
See page 1253

$\lambda = 405 \text{ nm}$, $P = 5 \text{ mW}$, Single Mode Sanyo DL3146-151

- Ø5.6 mm Package
- 405 nm (Typical) Wavelength
- 5 mW Output Power (CW)
- 35 mA (Typical) Threshold Current

Pin Description

- 1 laser anode
- 2 common case (cathode)
- 3 monitor diode anode



ITEM #	PRICE 1-5 PCS	PRICE 6-10 PCS	PRICE 11-20 PCS	DESCRIPTION
DL3146-151	CALL	CALL	CALL	Sanyo 405 nm, 5 mW

Maximum Ratings ($T_c = 25^\circ\text{C}$)

CHARACTERISTIC	SYMBOL	MAX RATING
Optical Output Power (CW)	P_o	7 mW*
LD Reverse Voltage	$V_{R(LD)}$	2 V
PD Reverse Voltage	$V_{R(PD)}$	30 V
Operation Case Temperature	T_{op}	0 to 60 °C
Storage Temperature	T_{stg}	-40 to 85 °C

*5 mW Typical

Characteristics ($T_c = 25^\circ\text{C}$, $P = 5 \text{ mW}$)

CHARACTERISTIC	SYMBOL	MIN	TYP	MAX
Lasing Wavelength	λ_p	400 nm	406 nm	413 nm
Threshold Current	I_{th}	—	33 mA	55 mA
Operating Current	I_{op}	—	40 mA	60 mA
Operating Voltage	V_{op}	—	5.0 V	6.0 V
Beam Divergence (FWHM)	$\theta_{//}$	6°	8°	14°
	θ_{\perp}	16°	20°	24°
Slope Efficiency	η_s	0.5 mW/mA	0.8 mW/mA	—
Monitor Current	I_m	0.1 mA	0.2 mA	1.0 mA

Note: All data are presented as typical unless otherwise specified.

$\lambda = 405 \text{ nm}$, $P = 10 \text{ mW}$, Single Mode Sanyo DL4146-101S

Maximum Ratings ($T_c = 25^\circ\text{C}$)

CHARACTERISTIC	SYMBOL	MAX RATING
Optical Output Power (CW)	P_o	20 mW*
LD Reverse Voltage	$V_{R(LD)}$	2 V
PD Reverse Voltage	$V_{R(PD)}$	—
Operation Case Temperature	T_{op}	0 to 75 °C
Storage Temperature	T_{stg}	-40 to 85 °C

*10 mW Typical

Characteristics ($T_c = 25^\circ\text{C}$, $P = 10 \text{ mW}$)

CHARACTERISTIC	SYMBOL	MIN	TYP	MAX
Lasing Wavelength	λ_p	395 nm	405 nm	415 nm
Threshold Current	I_{th}	—	26 mA	50 mA
Operating Current	I_{op}	—	35 mA	60 mA
Operating Voltage	V_{op}	—	4.8 V	5.6 V
Beam Divergence (FWHM)	$\theta_{//}$	6°	8.5°	12°
	θ_{\perp}	16°	19°	23°
Slope Efficiency	η_s	0.7 mW/mA	1.1 mW/mA	—
Monitor Current	I_m	0.1 mA	0.2 mA	0.5 mA

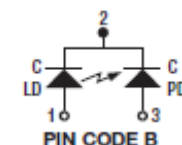
Note: All data are presented as typical unless otherwise specified.



NEW
product

Pin Description

- 1 laser anode
- 2 common case (cathode)
- 3 monitor diode anode







- Ø5.6 mm Package
- 10 mW (Typical) Output Power (CW)
- 1.1 mW/mA (Typical) Slope Efficiency

ITEM #	PRICE 1-5 PCS	PRICE 6-10 PCS	PRICE 11-20 PCS	DESCRIPTION
DL4146-101S	CALL	CALL	CALL	Sanyo 405 nm, 10 mW

VIS semiconductor lasers example LASOS

Laser diode modules fiber coupled

	VLD F 				BLD F 			GLD F 	RLD F 			
Wavelength [nm]	405	415	425	445	460	473	488	515	638	642	660	685
Output power [mW]	50	50	50	40	40	35	30	10	50	60	50	25
Fiber Coupling	Pigtail											
Fiber type	Single mode, polarization maintaining											
Fiber length	2 m, others on request											
Fiber connector	FC 8° polish, others on request											
Fiber jacket	Standard: 3 mm PVC (PVC)											

1kW, Fiber-Coupled, Multi-Bar Module



Electrical Parameters¹

Power Conversion Efficiency	%	35%
Threshold Current (I_{TH})	A	<8
Operating Current (I_{OP})	A	<75
Operating Voltage (V_{OP})	V	<48

Thermal Parameters

Operating Temperature ^{2, 3, 4}	°C	+20 to +25
Storage Temperature	°C	0 to +55
Flow	L/h	500
Operating Water Temperature	°C	20 to 25
Purity	µm	10 / deionized
Recommended Cooling Capacity	W	2500

1kW, Fiber-Coupled, Multi-Bar Module



Optical Parameters		Units	
Center Wavelength (Range) ^{1, 3}	nm	976	
Center Wavelength Tolerance	nm	±3	
Output Power ³	W	1000	
Spectral Width (FWHM)	nm	5	
Slope Efficiency	W/A	16	
Wavelength Temp. Coefficient ²	nm/°C	~0.38	
Fiber Parameters			
Numerical Aperture	NA	0.2	0.12
Fiber Core Diameter	µm	400	800
Fiber Connector		QBH or LLK-HP (Q5)	QBH or LLK-HP (Q5)